L Number	Hits	Search Text	DB	Time stamp
18	2847	(Ta or tantalum or TaN or "tantalum nitride") same mask	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:17
19	2847	(Ta or tantalum or TaN or "tantalum nitride") same (mask or "hard mask")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:15
20	27150	(CO or "carbon monoxide") same (ammonia or "NH.sub.3")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:58
21	7	(CO or "carbon monoxide") same (ammonia or "NH.sub.3") same (Ta or tantalum or TaN or "tantalum nitride") same etch$3	USPAT; EPO; JPO; IBM_TDB	2003/03/25 08:56
22	288	(CO or "carbon monoxide") same (ammonia or "NH.sub.3") same (Ta or tantalum or TaN or "tantalum nitride")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 08:57
23	1503	(Ta or tantalum or TaN or "tantalum nitride") same (mask or "hard mask") same etch$3	USPAT; EPO; JPO; IBM_TDB	2003/03/25 09:02
25	25	((Ta or tantalum or TaN or "tantalum nitride") same (mask or "hard mask")) and ((CO or "carbon monoxide") same (ammonia or "NH.sub.3"))	USPAT; EPO; JPO; IBM_TDB	2003/03/25 09:12
26	13048	(CO or "carbon monoxide") with (ammonia or "NH.sub.3")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 09:49
32	269	(CO or "carbon monoxide") same (ammonia or "NH.sub.3") same etch$3	USPAT; EPO; JPO; IBM_TDB	2003/03/25 09:50
33	1243	(Ta or tantalum or TaN or "tantalum nitride") with (mask or "hard mask")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:21
34	4093	"carbon monoxide" same (ammonia or "NH.sub.3")	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:16
37	610	((Ta or tantalum or TaN or "tantalum nitride") with (mask or "hard mask")) same etch$3	USPAT; EPO; JPO; IBM_TDB	2003/03/25 10:22
38	14	(CO or "carbon monoxide") same (ammonia or "NH.sub.3") same (metal or conductive) same etch$3 same (mask or masking or masked)	USPAT; EPO; JPO; IBM_TDB	2003/03/25 11:00
39	53	(("carbon monoxide") with (ammonia or "NH.sub.3")) and (metal or conductive) and etch$3 and (mask or masking or masked)	USPAT; EPO; JPO; IBM_TDB	2003/03/25 11:06